

EXHIBIT A

1

Semiconductor Glossary

Semiconductor OneSource

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Term (Index)	Definition
cleaning	process of removing contaminants (particles as well as metallic and organic) from the surface of the wafer; can be implemented using liquid chemicals (wet cleaning) or gases (dry cleaning).
contaminant	
dry cleaning	
metallic contaminant	
organic contaminant	
particle	

wet cleaning

supercritical fluid

Term (Index)

Definition

dry cleaning

AHF, anhydrous HF

cryogenic aerosol

high velocity frozen particles of inert gases such as CO₂ and Ar; used to remove particles from the wafer surface.

hydrogen reduction, H₂

during anneal in H₂ ambient at temperature exceeding 900 deg. C.

UV/Cl₂

Term (Index)	Definition
Spin cleaning	spinning wafer is subjected to interactions with liquid cleaning solutions.
Term (Index)	Definition
wet cleaning	
APM	
DHF	dilute HF; SiO ₂ etching solution of 49% HF in water; typical mixture: 1 part HF : 100 parts H ₂ O.
dry cleaning	
HPM	
megasonic agitation, megasonic scrubbing	

ozonated water	
IMEC clean	SOM+APM+dHF/HCl Reference: IMEC
supercritical fluid	

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